

Korean International Semiconductor Conference & Exhibition on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[TuB2]	Sustainable	Ftch
LUCZ	Justaniable	LCOIL

Session Date November 11 (Tue.), 2025

Session Time 14:50-16:20

Session Room B (Grand Ballroom 1, 2F)

[TuB2-1] [Invited] 14:50-15:20

Low-GWP Cyclic Etching of SiO₂ Contact Holes Using Heptafluoropropyl Methyl Ether Sanghyun You and Chang-Koo Kim (Ajou Univ., Korea)

[TuB2-2] 15:20-15:35

Low Global Warming C₅F₁₀O/H₂O Plasma for Low Temperature Etching of SiO₂ and Si₃N₄ Daeun Hong, Sumin Park, Eunsu Lee, and Heeyeop Chae (Sungkyunkwan Univ., Korea)

[TuB2-3] 15:35-15:50

Etching Characteristics of SiO_2 Using $PF_5 + X(C_4F_6 \& C_4F_8)$ Plasma Chemistries with ACL Mask Ho June Chang, Byeongho Song, HyunJun Kim, Jeongwoon Bae, and Kyongnam Kim (Deajeon Univ., Korea)

[TuB2-4] 15:50-16:05

Comparative Study of C₃F₆ and CF₄ for Sustainable Plasma Etching of SiO₂ Inkyoung Cho and Chang-Koo Kim (Ajou Univ., Korea)

[TuB2-5] 16:05-16:20

Comparison of Etching Characteristics and Environmental Impact of Fluorocarbon Isomers in High Aspect Ratio (HAR) Etching Processes

Seyoung Choi, Chanhyuk Choi, Myeongho Park, Junsoo Lee, Akihide Sato, Sungtaek Kim, Dongwoo Kim, and Geunyoung Yeom (Sungkyunkwan Univ., Korea)